

Notice of References Cited	Application/Control No. 10/765,647	Applicant(s)/Patent Under Reexamination MIRKARIMI, LAURA WILLS	
	Examiner DuyVu n. Dèo	Art Unit 1765	Page 1 of 1

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	C	US-6,069,035	05-2000	O'Donnell et al.	438/220
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NON-PATENT DOCUMENTS

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*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)
Dates in MM-YYYY format are publication dates. Classifications may be US or foreign.